

This listing of claims will replace all prior versions, and listings of claims in the application:

LISTING OF CLAIMS:

1. (Currently Amended) An electron beam recording substrate where electron beam information recording is carried out comprising:

a substrate main body;

a resist film relative to the substrate main body; and

a surface layer area ~~including at least two layers of thin film in between the substrate main body and the resist film, wherein the layer adjacent to the resist film has a smaller average distance λ than the layer adjacent to the substrate main body, the layers are made of materials~~ a material containing at least one of elements with atomic numbers 21, 23, 25 to 36, 38 to 41, 43 to 48, 50 to 54, 56 to 72, 75 to 78, 80 and 82 to 83 by 50 wt% or greater that suppress suppresses enlargement of a scattering distribution diameter of electrons spread inside by irradiation of an electron beam from a resist film side.

2. (Original) The electron beam recording substrate according to claim 1, wherein the substrate main body is positioned on a side opposite to said resist film with respect to said surface layer area.

3. (Original) The electron beam recording substrate according to claim 1, wherein said electron beam recording substrate is made only of a same material as said material for said surface layer area.